

Session Title:	[MF2] Analysis I
Session Date:	November 14 (Mon.), 2022
Session Time:	15:00-17:10
Session Room:	Room F (Sicily Room, 1F)
Session Chair:	Prof. Hyungtak Seo (Ajou Univ., Korea)

[MF2-1] [Invited] 15:00-15:30

Methodologies in Determining Physical Characterization of Semiconductor Process Using In-line Analysis Tools

Jae-Hyun Kim (SK hynix, Korea)

[MF2-2] [Invited] 15:30-16:00

Precise Spectroscopic Analysis on Ultrathin Oxide Layer and Interfaces for Advanced ICs and Emerging Devices

Hyungtak Seo, Yeongwhan Ahn, Jiwoong Kim, Seokwon Lim, Yerin Jeon, and Jisoo Kim (Ajou Univ., Korea)

[MF2-3] [Invited] 16:00-16:30

How to Implement Thin Film Device Characterization to Accelerate Manufacturing R&D – Much Faster, Cheaper but More Accurate

Joon-Young (Albert) Choi (SurplusGLOBAL Inc., Korea)

[MF2-4] 16:30-16:50

Non-Destructive Local Defect Monitoring of Semiconductor Devices by Microsphere-Assisted Small Spot Spectroscopic Reflectometry

Kwangrak Kim, Soonyang Kwon, Jangryul Park, Youngsun Choi, Jiwoong Kim, Myungjun Lee, and Changhun Choi (Samsung Electronics Co., Ltd., Korea)

[MF2-5] 16:50-17:10

Real-Time Measurement of Contaminant Particles in Semiconductor Process

Jihun Mun and Sang-Woo Kang (KRISS, Korea)